

Search Notes

Application/Control No.

09/484,303

Examiner

W. David Coleman

Applicant(s)/Patent under
Reexamination

AHN ET AL.

Art Unit

2823

SEARCHED

Class	Subclass	Date	Examiner
438	643 686 627	4/26/05	WDC
438	650	1	1

INTERFERENCE SEARCHED

Class	Subclass	Date	Examiner
438	643	4/26/2005	WDC

**SEARCH NOTES
(INCLUDING SEARCH STRATEGY)**

	DATE	EXMR
EAST 2.0.1 Applicant forms a single diffusion barrier after forming a conductive plug and then covers the barrier with cont.	4/26/2005	WDC
a conductive line for metallization of an integrated circuit.	4/26/2005	WDC